

In re: Chung et al.
Serial No.: 10/047,706
Filed: Chung et al.
Page 2

Applicants also request entry of the Supplemental Information Disclosure Statement and accompanying PTO Form-1449 submitted herewith.

In view of the above, Applicants respectfully request favorable examination and allowance of the present application.

Respectfully submitted,



Mitchell S. Bigel
Attorney for Applicant
Registration No. 29,614

Customer Number:

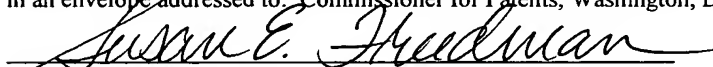


20792

PATENT TRADEMARK OFFICE

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, Washington, DC 20231, on March 14, 2002.



Susan E. Freedman

Date of Signature: March 14, 2002

In re: Chung et al.
Serial No.: 10/047,706
Filed: Chung et al.
Page 3

VERSION WITH MARKINGS TO SHOW CHANGES MADE

In the Specification:

The paragraph beginning at page 13, line 11, has been replaced with the following paragraph:

According to Si-woo [Lee] Rhee et al., "Chemical Vapor Deposition Precursors for (Ba, Sr)TiO₃ Films", 6th Korean Semiconductor Seminar, the deposition of Ti may be carried out using the surface reaction as a rate determining step, and high coverage may be achieved by virtue of the surface movement of Ti.